

METHOD OF FORMING DUAL DAMA- SCENE STRUCTURES

Abstract

A method of forming at least one wire on a substrate comprising at least one conductive region is provided. An insulating layer is disposed on the substrate. The method includes forming a hard mask layer on the insulating layer followed by forming at least one recess by removing portions of the hard mask layer and the insulating layer, forming a light blocking layer on the hard mask layer and the recess, and the light blocking layer and the hard mask layer forming a composite layer, forming a gap filling layer filling up the recess on the light blocking layer, forming a photoresist layer on the gap filling layer, aligning a photo mask with the recess by utilizing the composite layer as a mask, and performing an exposure/ development process to form at least one pattern above the recess in the photoresist layer.